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(12) **United States Design Patent** (10) **Patent No.:** **US D793,572 S**
Kozuka et al. (45) **Date of Patent:** **** Aug. 1, 2017**

(54) **ELECTRODE PLATE FOR PLASMA PROCESSING APPARATUS**

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(**) Term: **15 Years**

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(30) **Foreign Application Priority Data**

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(51) **LOC (10) Cl.** **24-02**

(52) **U.S. Cl.**
USPC **D24/224**

(58) **Field of Classification Search**
USPC D24/224, 107, 216; D27/227; D23/200,
D23/213, 214, 215, 222, 223, 229, 283;
D15/138; D13/182, 123; 138/144,
138/144.1; 239/548
CPC .. B05B 1/00; B05B 1/04; B05B 1/005; B05B
1/14; A47K 3/00
See application file for complete search history.

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(57) **CLAIM**

The ornamental design for an electrode plate for plasma processing apparatus, as shown and described.

DESCRIPTION

FIG. 1 is a front view of an electrode plate for plasma processing apparatus of the present invention.

FIG. 2 is a rear view thereof.

FIG. 3 is a top plan view thereof.

FIG. 4 is a bottom view thereof.

FIG. 5 is a right side view thereof.

FIG. 6 is a left side view thereof.

FIG. 7 is a perspective view thereof.

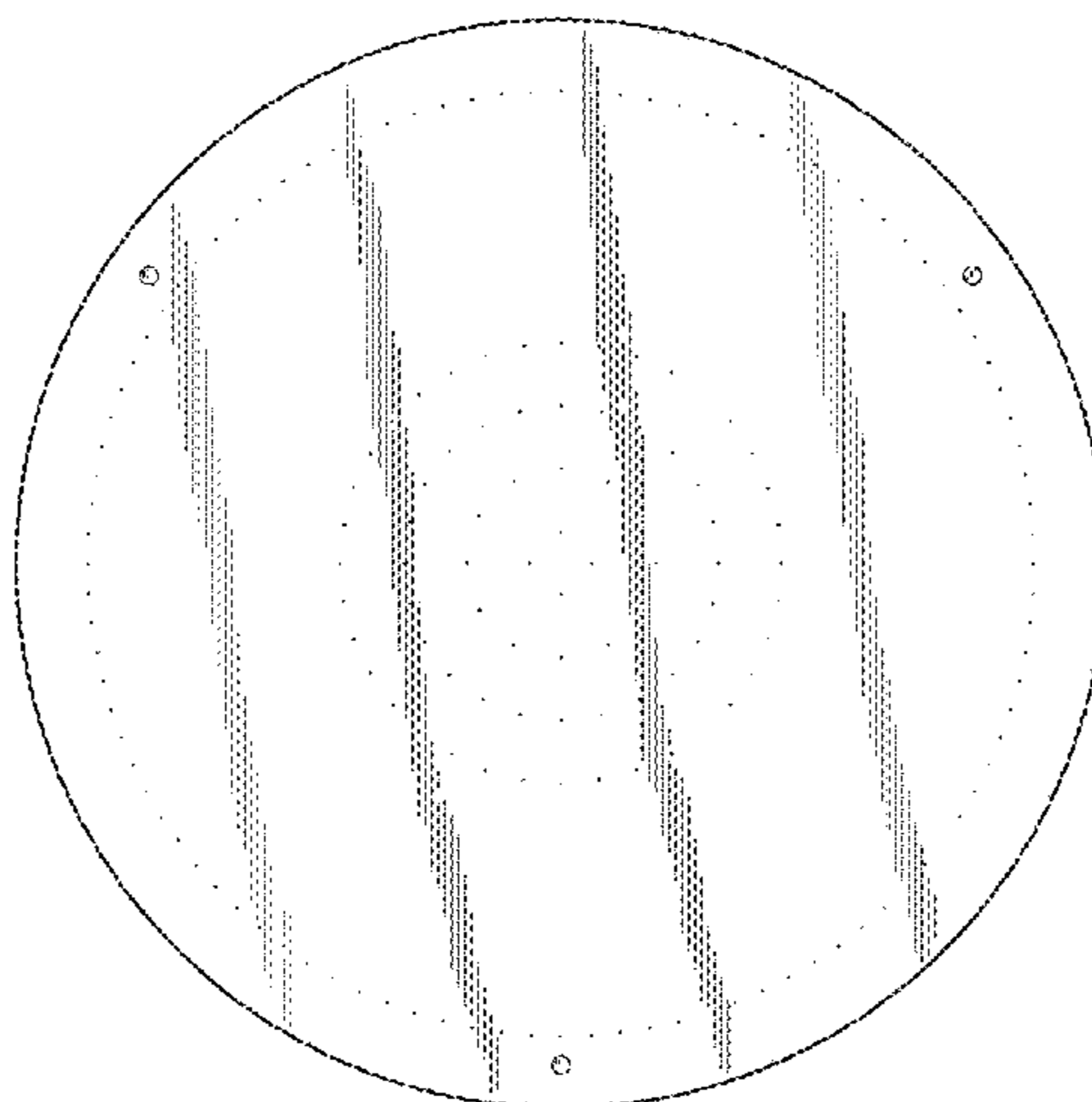
FIG. 8 is a sectional view of the electrode plate for plasma processing apparatus taken along section line 8-8 of FIG. 4.

FIG. 9 is an enlarged view of the portion indicated by arrows 9-9 of the electrode plate for plasma processing apparatus of FIG. 8; and,

FIG. 10 is a reference view of the electrode plate for plasma processing apparatus in use, wherein the electrode plate for plasma processing apparatus is used in the bottom part of a shower head, that is arranged to face a susceptor.

The features shown in broken lines depict environmental subject matter only and form no part of the claimed design.

1 Claim, 10 Drawing Sheets



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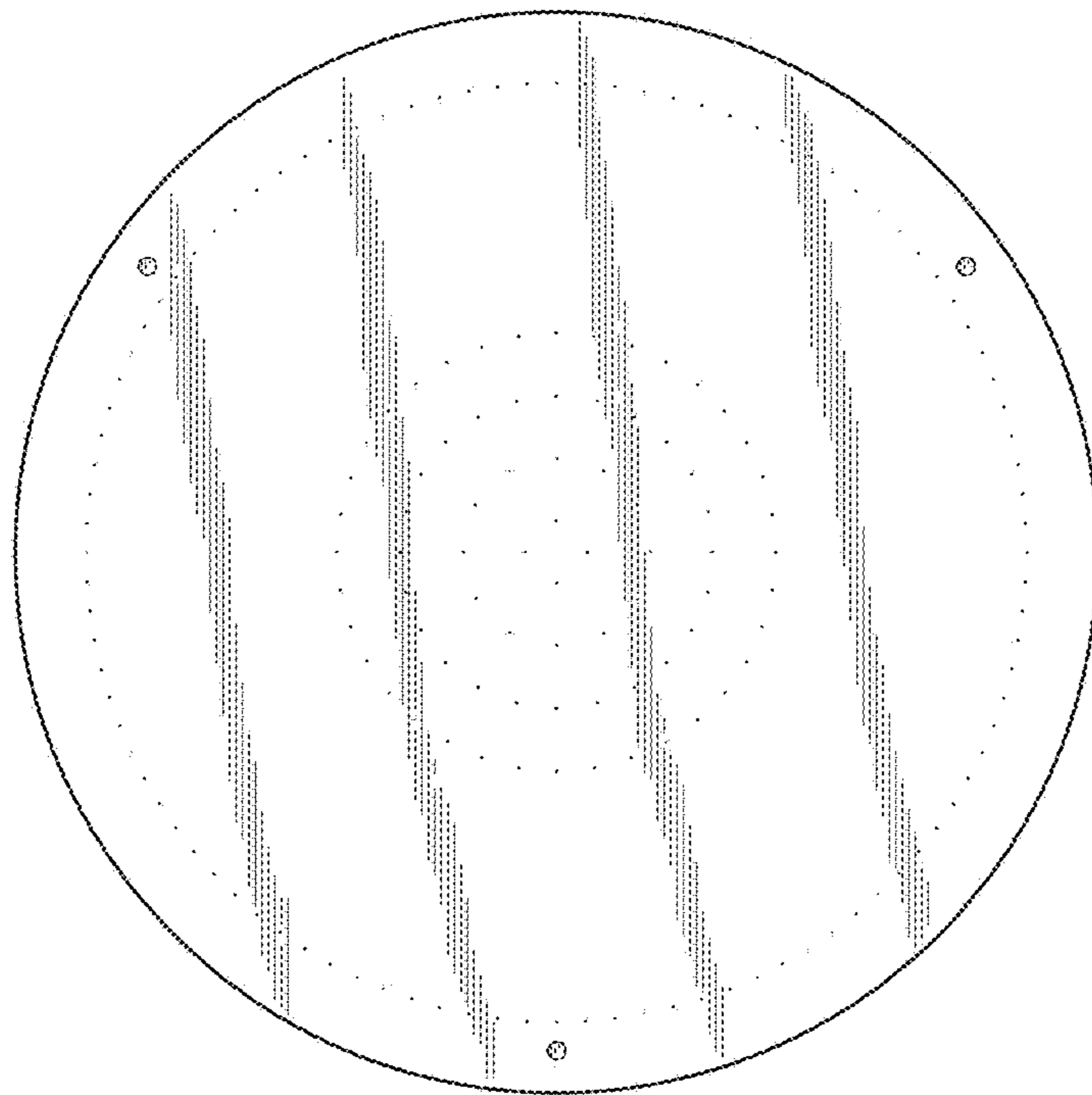


FIG. 1

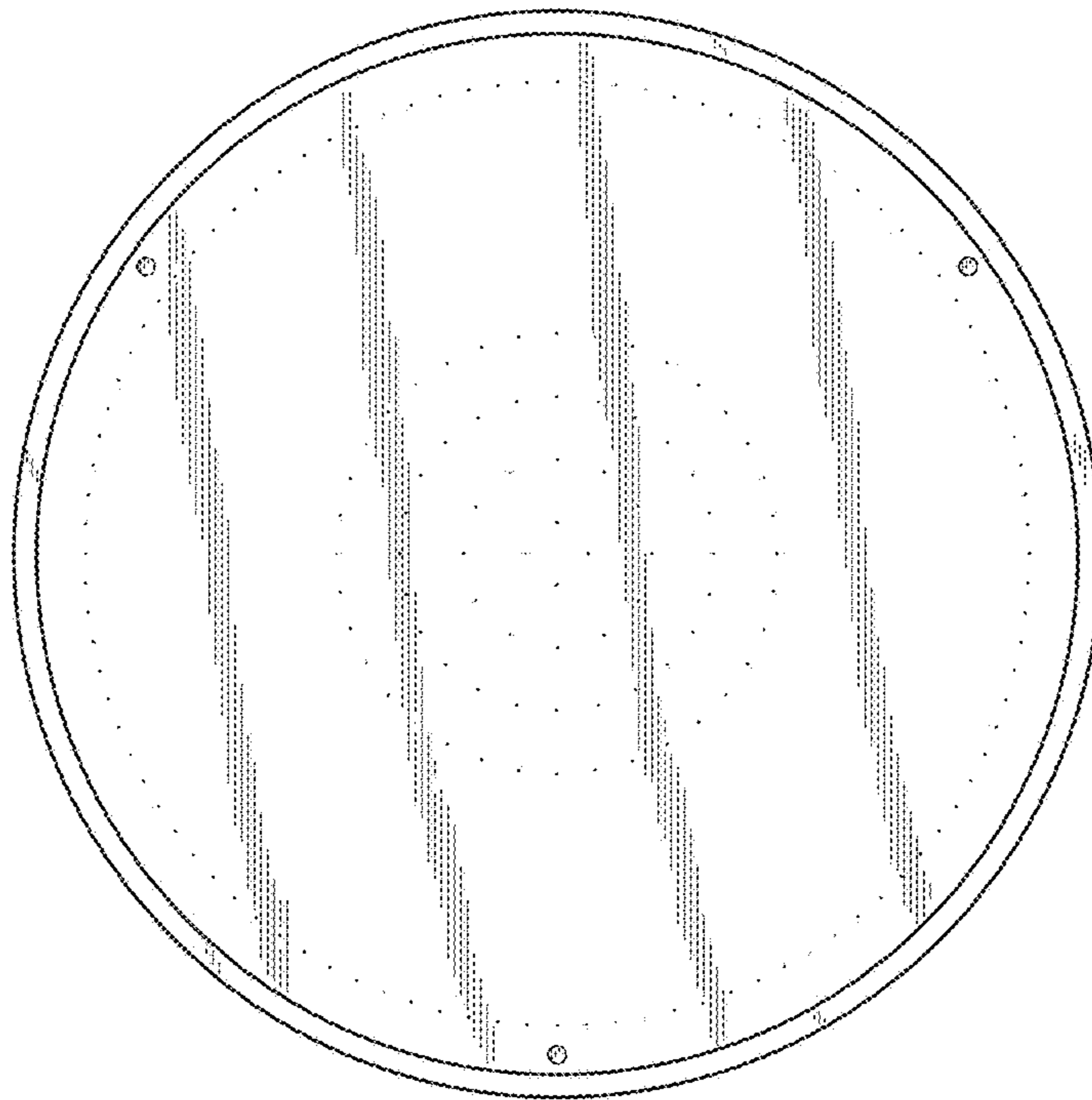


FIG. 2

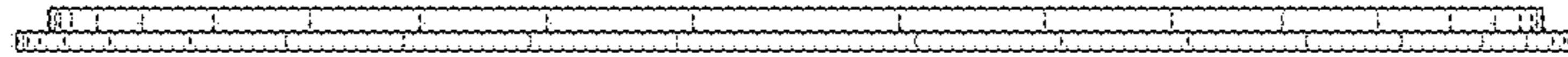


FIG. 3

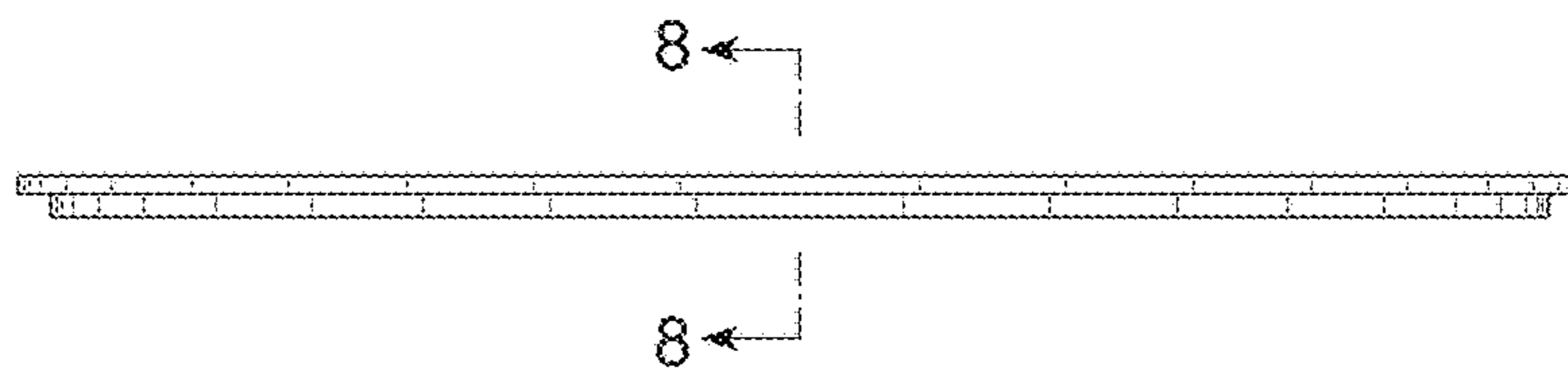


FIG. 4

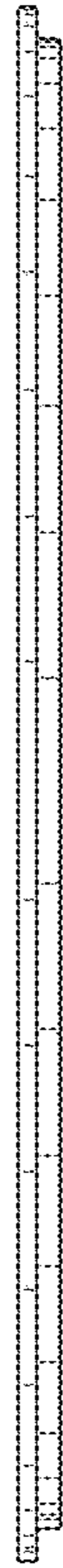


FIG. 5

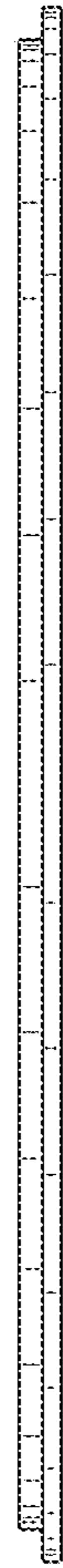


FIG. 6

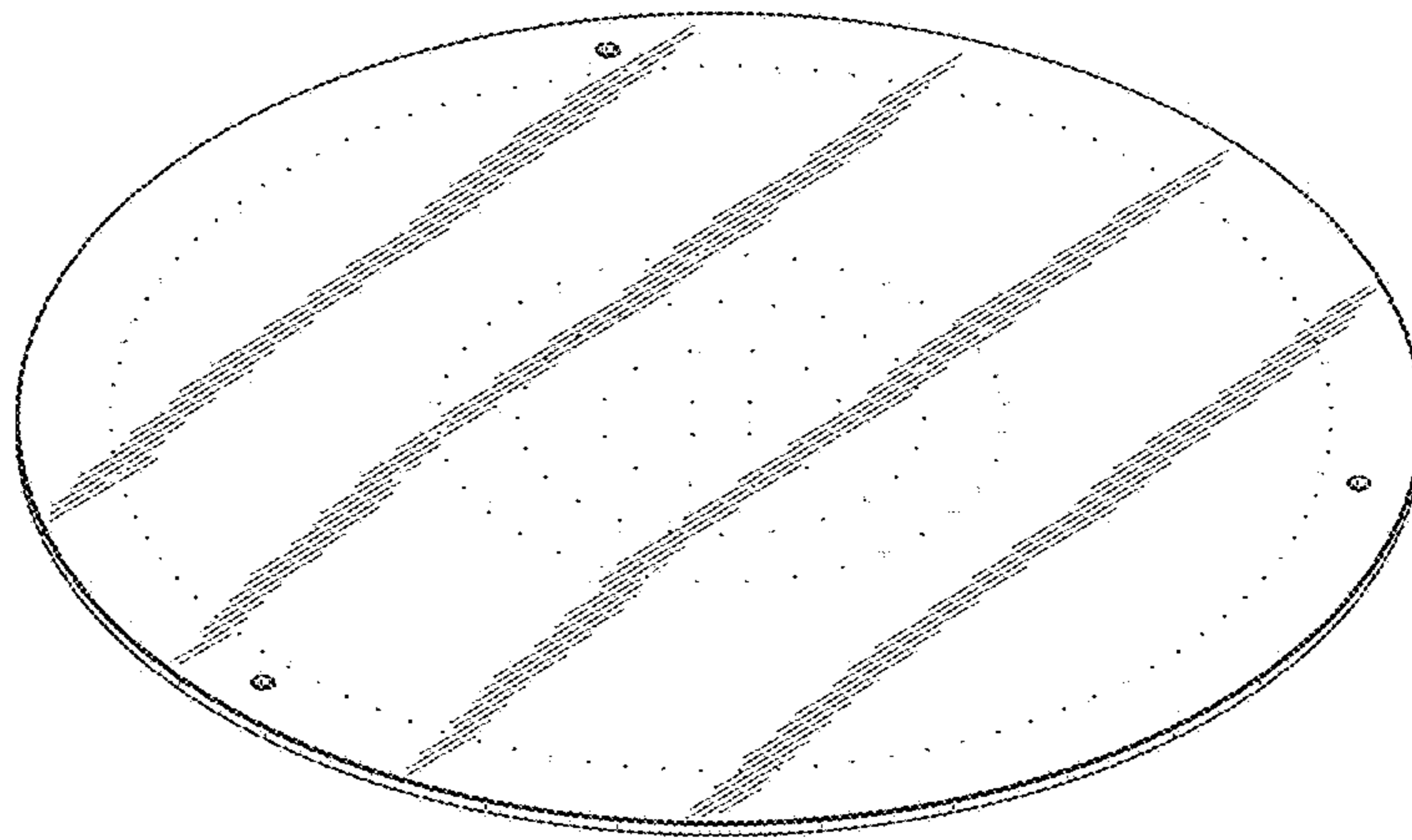


FIG. 7

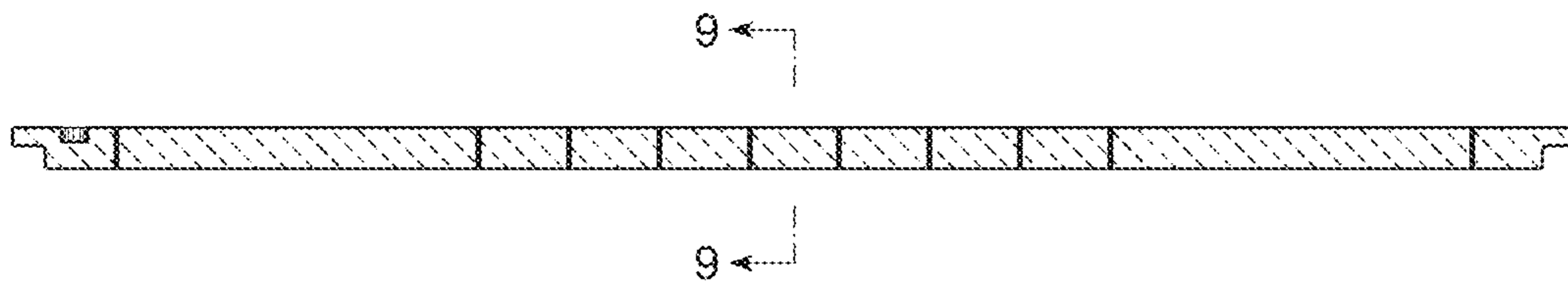


FIG. 8

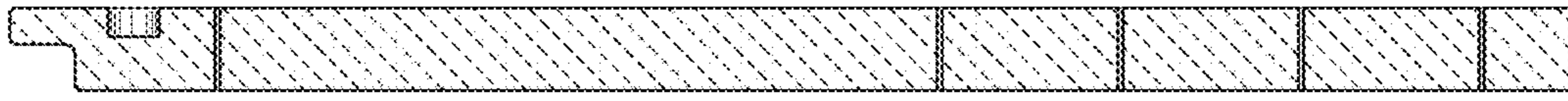


FIG. 9

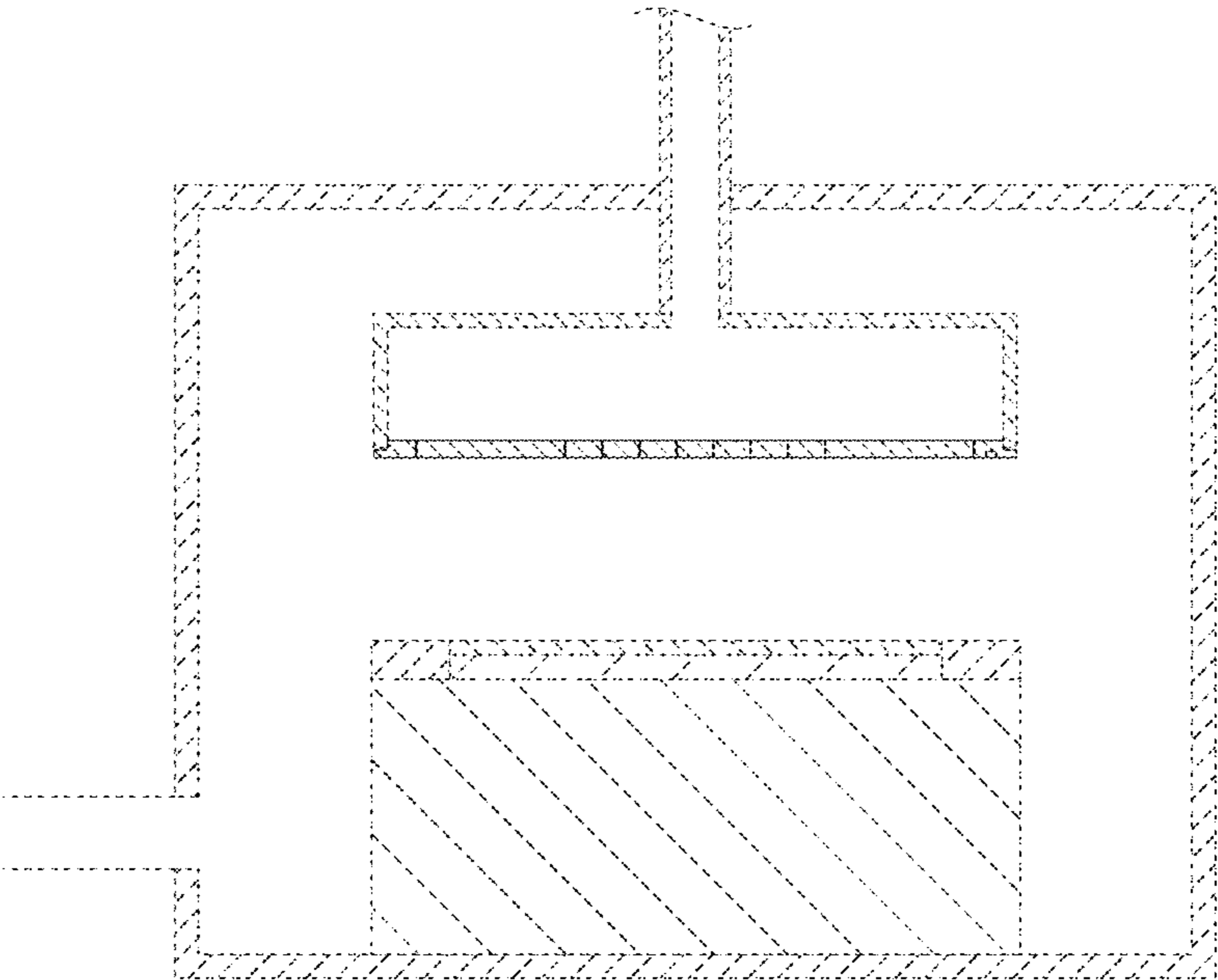


FIG. 10